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PATENT NUMBER

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U.S. UTILITY Patent Application

4 O.I.P.E. LPATENT DATE

SCANNED SECH QA. CHI

APPLICATION NO. 09/917697 CLASS SUBCLASS ART UNIT EXAMINER - 2812

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Microlithographic device, microlithographic assist features, system for forming contacts and other structures, and method of determining mask patterns

ORIGINAL CROSS REFERENCE(S)

CLASS SUBCLASS CLASS SUBCLASS (ONE SUBCLASS PER BLOCK)

INTERNATIONAL CLASSIFICATION

Continued on Issue Slip Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
The term of this patent subsequent to(date)	(Assistant Examiner) (Date)		NOTICE OF ALLOWANCE MAILED		
has been disclaimed.					
The term of this patent shall not extend beyond the expiration date					
of U.S Patent. No			ISSUE FEE		
				Amount Due	Date Paid
	(Primary Examiner) (Date)				
The terminalmonths of this patent have been disclaimed.				ISSUE BAT	CH NUMBER
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